

Nanoscale selective deposition of TiO_2 using e-beam patterned polymeric inhibition layers and TDMAT precursor

Ali Haider, Mehmet Yilmaz, Petro Deminskyi, Hamit Eren, Necmi Biyikli

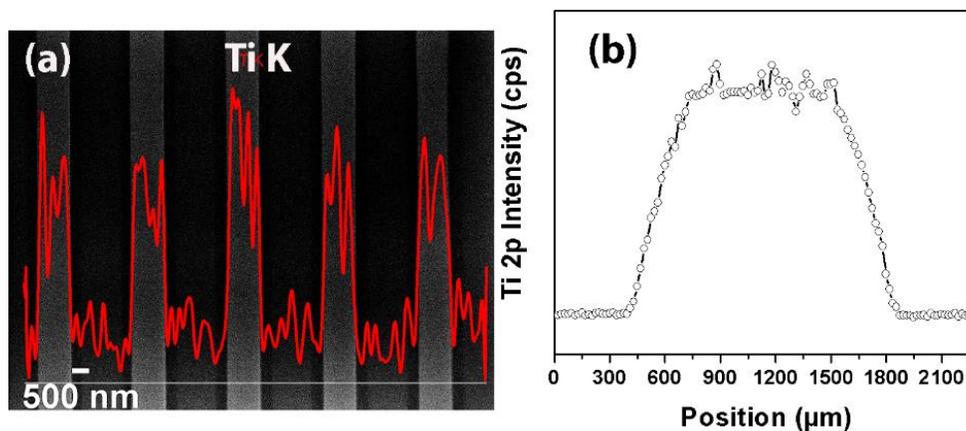


Figure 1. (a) EDX Ti K line scan obtained from self-aligned deposited nm-scale TiO_2 line features, (b) XPS Ti2p line scan obtained from mm-scale TiO_2 pattern formed on Si (100).

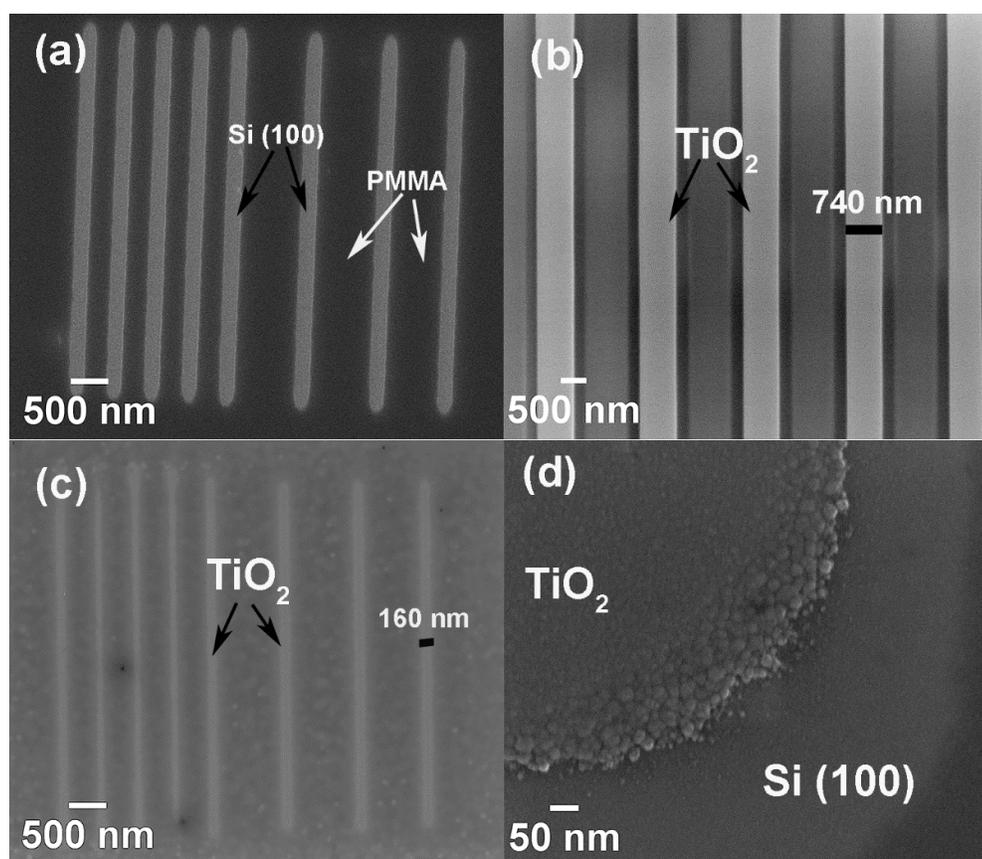


Figure 2. SEM images of (a) e-beam exposed and post developed PMMA, (b) and (c) TiO_2 patterns grown on patterned PMMA/Si(100) surface after the removal of PMMA, (d) interface between TiO_2 pattern and Si(100).